



Reg. No. :

Name :

Third Semester B.Tech. Degree Examination, November 2013
(2008 Scheme)

08.302 : SOLID STATE DEVICES (TA)

Time : 3 Hours

Max. Marks : 100

PART – A



Answer **all** questions. **Each** question carries 4 marks.

1. Derive the continuity equation for holes and electrons in a semi conductor.
2. With neat diagram explain the Fermi-Dirac distribution applied to semi conductors.
3. A GaAs sample is doped so that the electron-hole components of currents are equal in an applied electric field. Calculate the equilibrium electron-hole concentrations, the net doping and the sample resistivity at 300 K
 $\mu_n = 8500 \text{ cm}^2 / \text{Vs}$ $\mu_p = 400 \text{ cm}^2 / \text{Vs}$ $n_i = 1.79 \times 10^6 \text{ cm}^{-3}$.
4. With neat diagram distinguish between direct and indirect band semiconductor.
5. Derive the junction capacitance of a linearly graded junction.
6. Explain with neat diagram Avalanche Breakdown.
7. An n channel Si JFET has $N_d = 10^{16} \text{ cm}^{-3}$ $N_a = 10^{19} \text{ cm}^{-3}$ and $a = 1 \text{ } \mu\text{m}$. Determine the
 - a) built in voltage
 - b) pinch off voltage.
8. What is a punched through diode ? What are its advantage ?
9. Explain the C-V characteristics of ideal MOS system.
10. Explain the principle of operation of JFET.



PART – B

Answer **any two** questions from **each** Module. **Each** question carries **10** marks.

Module – I

11. State and derive Einstein's relation.
12. Explain Hall effect. Explain the procedure to measure majority carrier concentration and mobility of a semi conductor specimen.
13. Intrinsic Ge sample at room temperature has resistivity of $50 \Omega \text{ cm}$. The sample is doped to the extend of $6 \times 10^{13} \text{ As atoms/cm}^3$ and $10^{14} \text{ Boron atoms per cm}^3$. Find the conduction current density if an electric field of 4 V/cm is applied across the sample $\mu_n = 3800 \text{ cm}^2 / \text{Vs}$ $\mu_p = 1800 \text{ cm}^2 / \text{Vs}$.

Module – II

14. Derive expressions for injection efficiency transport factor, α and β of a p-n-p transistor operating in the active region in terms of the doping and dimensions of the different regions of the transistor.
15. Define the figure of merit of a BJT. Derive the expression for the same.
16. a) Explain the principle of operation of Schottky diode and derive the current equation.
 b) An ideal Silicon abrupt p-n junction has $N_A = 10^{16}$, $N_D = 10^{14} \text{ Cm}^{-3}$. $\tau_n = \tau_p = 0.1 \mu\text{s}$ $A = 10^{-3} \text{ cm}^2$, $D_p = 10 \text{ cm}^2/\text{s}$. $D_n = 24 \text{ cm}^2/\text{s}$. Determine the dynamic forward resistance of the diode at 300 K with forward voltages of
 a) 0.5 v b) 0.6 V.

Module – III

17. Explain the principle of operation of an SCR.
18. a) An n channel Si JFET has $N_A = 10^{19} \text{ cm}^{-3}$ $N_D = 10^{15} \text{ cm}^{-3}$ and $a = 4 \mu\text{m}$. Determine at 300 K
 a) pinch-off voltage
 b) the gate bias required to make the thickness of the undepleted channel equal to $1 \mu\text{m}$ with $V_{DS} = 0$.
 b) Define the threshold voltage of ideal MOS capacitor.
19. Explain the structure and principle of operation of depletion mode MOSFET. Derive expression for drain current.